

Listing of Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1 – 22 (cancelled)

23. (new) An aqueous developer composition comprising an alkaline developer component selected from alkali silicates, alkali hydroxides, Na_3PO_4 , K_3PO_4 , NR_4OH , wherein each R is independently selected from C_1 - C_4 alkyl groups and C_1 - C_4 hydroxyalkyl groups, and mixtures thereof in the water and having a pH of 13 to 14, and further comprising a stabilizer comprising M_2CO_3 , wherein each M is independently selected from Li, Na, K and NR'_4 and each R' independently represents H or C_1 - C_4 alkyl, wherein the amount of the stabilizer is such that the amount of the carbonate anion is 1.5 to 20 wt-%, based on the total weight of the developer composition.
24. (new) The developer composition of claim 23 wherein the stabilizer is Na_2CO_3 .
25. (new) The developer composition of claim 23 wherein the amount of carbonate anion is 2.5 to 12 wt-%.
26. (new) The developer composition of claim 23 wherein the alkaline developer component comprises an alkali silicate.
27. (new) The developer composition of claim 23 additionally comprising one or more additives selected from glycols, surfactants, anti-foaming agents, biocides, complexing agents and organic solvents.
28. (new) A process for producing a developer composition according to claim 23, comprising
- (a) providing water,
 - (b) dissolving such an amount of an alkaline developer component

- selected from alkali silicates, alkali hydroxides, Na_3PO_4 , K_3PO_4 , NR_4OH , wherein each R is independently selected from C_1 - C_4 alkyl groups and C_1 - C_4 hydroxyalkyl groups, and mixtures thereof in the water provided in step (a) that a pH of from 13 to 14 is obtained, and
- (c) dissolving a stabilizer selected from M_2CO_3 , MHCO_3 , or a mixture of 2 or more thereof, wherein each M is independently selected from Li, Na, K and NR'_4 and each R' independently represents H or C_1 - C_4 alkyl, in the solution obtained in step (b) wherein the amount of the added stabilizer is such that the amount of the added carbonate anion is 1.5 to 20 wt-%, based on the total weight of the developer composition.
29. (new) The process of 28 wherein before or after the dissolution of the stabilizer at least one additive selected from glycols, surfactants, anti-foaming agents, biocides, complexing agents and organic solvents is added.
30. (new) A process for developing exposed printing plate precursors, comprising:
contacting a printing plate precursor with a developer composition as defined in claim 23.
31. (new) The process of 30 wherein the image-wise exposed printing plate precursor is not developable with an aqueous developer having a pH of below 12.
32. (new) The process of claim 30 wherein the printing plate precursor is a UV-sensitive positive working printing plate precursor or a heat-sensitive printing plate precursor.
33. (new) The process of claim 32 wherein the heat-sensitive coating of the printing plate precursor comprises a phenolic resin.
34. (new) A concentrate comprising the developer composition of claim 23 that has been concentrated up to 10 times.